ABSTRACT

The present invention relates to a temperature control system for controlling a temperature of a heat medium used for a semiconductor manufacturing apparatus, such as an etching apparatus, a CVD apparatus, or a PVD apparatus. The temperature control system (1) includes: a first circulation circuit (11) in which a first heat medium circulates; a second circulation circuit (12) in which a second heat medium circulates; a third circulation circuit (13) in which a third heat medium circulates; a cooling device (7) configured to cool the first heat medium flowing through the first circulation circuit (11); a heating device (8) configured to heat the second heat medium flowing through the second circulation circuit (12); a first heat exchanger (21) configured to exchange heat between the first heat medium and the third heat medium; and a second heat exchanger (22) configured to exchange heat between the second heat medium and the third heat medium. The first heat exchanger (21) and the second heat exchanger (22) are coupled in series by the third circulation circuit (13).

FIG. 1